

Notice of References Cited		Application/Control No. 10/594,282	Applicant(s)/Patent Under Reexamination ISHII ET AL.	
		Examiner Sin J. Lee	Art Unit 1795	Page 1 of 1

U.S. PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A US-6,093,517	07-2000	Ito et al.	430/270.1
*	B US-5,683,856	11-1997	Acrai et al.	430/270.1
C	US-			
D	US-			
E	US-			
F	US-			
G	US-			
H	US-			
I	US-			
J	US-			
K	US-			
L	US-			
M	US-			

FOREIGN PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
N					
O					
P					
Q					
R					
S					
T					

NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
U	Sakamizu et al ("Structural Design of Resin Matrix and Acid-labile Dissolution Inhibitor of Chemical Amplification Positive Electron-beam Resist for Gigabit Lithography", Journal of Photopolymer Science and Technology, Vol.11, No.4 (1998), pg.547-552.
V	
W	
X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.